Page 5, please replace paragraph [0020] as follows:

[0020] The method of manufacturing a photocatalytic colored member according to the present invention comprises the steps of: laminating a plurality of layers of thin-film layers of photocatalytic material and thin-film layers of support material, forming a plurality of openings through a plurality of layers of the multi-layer film by means of physical dry etching with argon ions or the like, and next, using wet etching to remove excess support material to form, on the rear surface side of the thin-film layers of photocatalytic material, vacant layers or spaces adjacent to remaining support material that are open to the outside.

Page 6, please replace paragraph [0029] as follows:

[0029] FIG. 4(a) is a perspective diagram showing the state wherein the surface area of the laminated thin-film layers of photocatalytic colored member according to the present invention becomes larger when going from the surface to lower layers.

Page 6, please replace paragraph [0031] as follows:

[0031] FIG. 4(c) is a perspective diagram showing the state wherein the surface area of the aforementioned laminated thin-film layers becomes smaller when going from the surface to lower layers.

Page 9, please replace paragraph [0044] as follows:

[0044] Thereafter, BHF is used to perform wet etching of the silicon dioxide film to form a vacant layer or space 10 on the back side of the thin-film layers of photocatalytic material 1. The thickness of this vacant layer 10 is the thickness of the silicon dioxide film serving as the layer of support material, so its thickness is $\lambda/4$.

Page 10, please replace paragraph [0048] as follows:

[0048] In addition, in the various aforementioned embodiments, the plurality of laminated thin-film layers of photocatalytic material 1 interspersed with thin-film layers of